AMENDMENTS TO THE CLAIMS

Please amend the claims as follows:

1. (currently amended) A method of depositing an organic material, comprising:

ejecting a carrier gas carrying an organic material from a nozzle at a flow velocity that is at least 10 % of the thermal velocity of the carrier gas, such that the organic material is deposited onto a substrate;

wherein ~~the dynamic pressure in~~ a region between the nozzle and the substrate surrounding the carrier gas has a dynamic pressure of ~~is~~ at least 1 Torr,

and wherein the organic material is transported by a transition flow regime or a free molecular flow regime.

2. (original) The method of claim 1, wherein the dynamic pressure is at least 10 Torr.

3. (currently amended) The method of claim 2, wherein a ~~the~~ background pressure ~~atmosphere is~~ of at least 5 Torr is provided.

4. (original) The method of claim 2, further comprising:

ejecting a guard flow from the nozzle.

5. (currently amended) The method of claim 4, wherein a ~~the~~ background pressure ~~atmosphere is~~ of ~~ambient atmosphere at~~ about 760 Torr is provided, and the background pressure is the ambient atmosphere.

6. (original) The method of claim 2, wherein the dynamic pressure of at least 10 Torr is affected by a guard flow ejected from the nozzle.

7. (currently amended) The method of claim 6, wherein the method is performed in ~~the background pressure is the base pressure of~~ a vacuum chamber at base pressure, ~~and is~~ thereby providing a background pressure of less than about 0.1 Torr.

8. (original) The method of claim 7, wherein the molecular weight of the organic material is greater than the molecular weight of the carrier gas.

9. (original) The method of claim 6, wherein the guard flow comprises a first gas, the carrier gas comprises a second gas, and the molecular weight of the first gas is greater than the molecular weight of the second gas.

10. (original) The method of claim 1, wherein the dynamic pressure is at least about 760 Torr.

11. (currently amended) A method of depositing an organic material, comprising:

ejecting a carrier gas carrying an organic material from the nozzle at a flow velocity that is at least 10 % of the thermal velocity of the carrier gas, such that the organic material is deposited onto a substrate;

providing a guard flow around the carrier gas,

wherein the organic material is transported by a transition flow regime or a free molecular flow regime.

12. (original) The method of claim 11, wherein the method is performed with a background pressure of at least about 760 Torr.

13. (original) The method of claim 11, wherein the method is performed in a glove-box without the use of a vacuum apparatus.

14. (currently amended) ~~A method of depositing an organic material, comprising:~~

~~ejecting a carrier gas carrying an organic material from the nozzle at a flow velocity that is at least 10 % of the thermal velocity of the carrier gas, such that the organic material is deposited onto a substrate;~~

The method of claim 1, wherein a ~~the~~ background pressure of ~~is~~ at least about 10e-3 Torr is provided.

15. (original) The method of claim 14, wherein the background pressure is at least 0.1 Torr.

16. (original) The method of claim 15, wherein the background pressure is at least 1 Torr.

17. (original) The method of claim 16, wherein the background pressure is at least 10 Torr.

18. (currently amended) The method of claim 17, wherein the background pressure is at least about 760 Torr.

19. (original) The method of claim 18, wherein the background pressure of at least about 760 Torr is provided by a glove box without the use of a vacuum apparatus.

20. (original) The method of claim 14, wherein the background pressure is achieved without the use of vacuum apparatus.

21-32. (canceled)